Notice of Allowability	Application No.	Applicant(s)		
	09/932,943	MINAMIHABA ET	MINAMIHABA ET AL.	
	Examiner	Art Unit		
	Hsien-Ming Lee	2823		
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.				
 This communication is responsive to 7/24/03 and 7/30/03. The allowed claim(s) is/are 18-37. The drawings filed on 8/21/01 are accepted by the Examinated Acknowledgment is made of a claim for foreign priority under a) All b) Some* c) None of the: All b) Some* c) None of the: Certified copies of the priority documents have 	ler 35 U.S.C. § 119(a)-(d) o	· ·		
3. Copies of the certified copies of the priority do		·	ation from the	
* Certified copies not received: 5. Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application). (a) The translation of the foreign language provisional application has been received. 6. Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.				
Applicant has THREE MONTHS FROM THE "MAILING DATE" of below. Failure to timely comply will result in ABANDONMENT of				
7. A SUBSTITUTE OATH OR DECLARATION must be submINFORMAL PATENT APPLICATION (PTO-152) which gives reas			NOTICE OF	
 8. CORRECTED DRAWINGS must be submitted. (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached 1) hereto or 2) to Paper No (b) including changes required by the proposed drawing correction filed, which has been approved by the Examiner. 				
(c) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No				
Identifying indicia such as the application number (see 37 CFR 1 each sheet.	.84(c)) should be written on	the drawings in the front (not th	ıe back) of	
9. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.				
Attachment(s)				
 1 Notice of References Cited (PTO-892) 3 Notice of Draftperson's Patent Drawing Review (PTO-948) 5 Information Disclosure Statements (PTO-1449), Paper No 7 Examiner's Comment Regarding Requirement for Deposit of Biological Material 	4∏ Intervie 6∏ Examir	of Informal Patent Application w Summary (PTO-413), Pape ner's Amendment/Comment ner's Statement of Reasons for	er No	

Application/Control Number: 09/932,943

Art Unit: 2823

DETAILED ACTION

Remarks

- 1. Applicants' cancellation to claims 1-17 is acknowledged.
- 2. Claims 18-37 are pending in the application.
- 3. The Final rejection is withdrawn in response to applicants' amendment after Final filed 7/24/03 and supplemental amendment after Final filed 7/30/03.

Allowable Subject Matter

- 4. Claims 18-37 are allowed.
- 5. The following is an examiner's statement of reasons for allowance:

The closest prior art or record, Wojtczak et al. to US 6,409,781 teach a method of manufacturing a semiconductor device, as set forth in Final rejection.

In contrast, Wojtczak et al. neither teach nor suggest teach subjecting said conductive material film to a chemical mechanical polishing (CMP) using a slurry comprising first colloidal silica particles whose primary particles have a diameter ranging from 5 to 20 nm and second colloidal silica particles whose primary particles have a diameter ranging from 20 nm to 50nm, wherein the weight ratio of the first colloidal silica particles is in the range of 0.6 to 0.9 based on a total weight of said first and second colloidal silica particles; that the slurry includes third particles formed of a material different from those of the first and second colloidal silica particles, to remove said conductive material film; and that the slurry contains a surfactant, which is dodecyl benzene sulfonate.

Thus, the instant invention is deemed to be directed to a nonobvious improvement over the prior art. The improvement comprises first, second and third particles with different particle

Application/Control Number: 09/932,943

Art Unit: 2823

size and materials and using dodecyl benzene sulfonate as a surfactant in the polishing slurry so

as to optimize and to precisely control polishing.

6. Any comments considered necessary by applicant must be submitted no later than the

payment of the issue fee and, to avoid processing delays, should preferably accompany the issue

fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for

Allowance."

7. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Hsien-Ming Lee whose telephone number is 703-305-7341. The

examiner can normally be reached on M-F (9:00 \sim 5:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Olik Chaudhuri can be reached on 703-306-2794. The fax phone number for the

organization where this application or proceeding is assigned is (703) 308-7722.

Any inquiry of a general nature or relating to the status of this application or proceeding

should be directed to the receptionist whose telephone number is 703-308-0956.

Hsien-Ming Lee

Page 3

Examiner

Art Unit 2823

Sep. 8, 2003

W. DAVID COLEMAN PRIMARY EXAMINER